

WEE™

Wafer Edge Exposure

COAT ■ DEVELOP ■ BAKE ■ WEE



WEE™ (Wafer Edge Exposure)

- Up to 15000 milliwatts per square centimeter exposure energy
- Programmable exposure dose
- Closed loop control of exposure dose
- Exposure dose traceable to NIST
- No need to handle, buy or swap masks. Pattern and wafer size is programmable
- Flat following exposure pattern
- Notched programmable exposure pattern available
- SECS/GEM Factory Automation Available
- System operates by “painting” the edge of the wafer with light
- Handles differing wafer sizes interchangeably and programmatically

Applications

*When removal of the edge bead in a precise and controlled way is a requirement, S-Cubed WEE is **THE INDUSTRY SOLUTION.***

S-Cubed System Features

- Small footprint
- Color LCD touchscreen
- One or two spin modules
- Unlimited process storage capabilities
- Remote data collection and control
- Stacked thermal modules
- Multiple size substrates without change
- Servo motion control
- Process substrates up to 300 mm
- Proven modular design
- Ultra high reliability

For more information on all products including the new Flexi™ system, the TruClean™ double sided scrubbing systems, and Cyclone™ spin processors, please visit our website: www.s-cubed.com.

S CUBED

Solid • Smart • Stable

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